



MicroTorr: Ambient Inline Purifiers

MicroTorr Features

MicroTorr Purifiers are the most complete and reliable solution for Point-of-Use (POU) gas purification. Combining A model size with a selection of gas-specific purification materials, MicroTorr purifiers can be tailored to many different customer applications, while maintaining impurity removal to part-per-Trillion (ppt) levels. Optional valves and a 0.003µm particle filter are available as well as custom subsystem configurations.

Product Highlights

- Reliability: Delivery of Ultra-High-Purity (UHP) gas for uncompromised process consistency and yield improvement. Inorganic active purification media means protection from hydrocarbon release.
- **Performance:** State of the art purification technology, low pressure drop, and long lifetimes.
- Environmentally Friendly: Most MicroTorr media are factory regenerable, minimizing potentially hazardous waste generation.
- Quality: Hardware assembly made of 316L stainless steel. All units are Helium leak checked, pressure tested, and analytically tested to part-per-trillion (ppt) levels.
- **Certified:** CE certification according to Pressure Equipment Directive (PED)
- **Support:** Lifetime estimation and regeneration service available through the SAES Pure Gas Global Support Network.





CLEAN, RELIABLE GAS

To select a Purifier

Choose:

- · Purifier Size
- Purification Media
- Optional 0.003µm Particle Filter (F)
- Optional Inlet and Outlet Isolation Valves (V)

Part Number Example

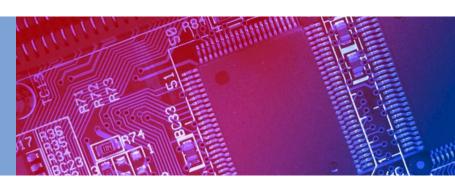
Size	Media	Particle Filter	Isolation Valves	Final Part Number
MC1-	302	F	V	MC1-302FV
MC3000-	902	F		MC3000-902F

Purifier Sizes

Model	Maximum Flow (slpm)	Average Flow (slpm)	Maximum Pressure (psig)	Connection Type	Diameter (inches [mm])	Face-to-Face (inches [mm])	Face-to-Face with valves (inches [mm])
MC1	5	0.5	1,000	1/4" VCR	1.5 [38.1]	3.31 [84.1]	8.91 [226.3]
MC45	10	1.5	1,000	1/4" VCR	1.5 [38.1]	4.5 [114.3]	10.10 [256.5]
MC50	10	1.5	1,000	1/4" VCR	1.5 [38.1]	5.0 [127]	10.60 [269.2]
MC190	50	5	250	1/4" VCR	2.0 [50.8]	8.2 [208.3]	13.80 [350.5]
MC200	50	5	250	1/4" VCR	2.0 [50.8]	6.3 [160]	11.90 [302.3]
MC400	60	9	250	1/4" VCR	3.0 [76.2]	8.2 [208.3]	13.80 [350.5]
MC450 / FT400	75	10	250	1/4" VCR	3.0 [76.2]	7.94 [201.7]	13.54 [343.9]
MC500	100	12	250	1/4" VCR	2.0 [50.8]	12.5 [317.5]	18.10 [459.7]
MC700	120	25	250	1/4" VCR	3.0 [76.2]	10.0 [254.0]	15.6 [396.2]
MC2525	300	80	250	1/4" VCR	4.0 [101.6]	17.3 [439]	23.2 [589]
MC1500	250	40	250	1/2" VCR	3.0 [76.2]	18.2 [462.3]	28.84 [732.5]
MC2550	500	80	250	1/2" VCR	4.0 [101.6]	17.6 [447]	28.2 [716]
MC3000	500	80	250	1/2" VCR	4.0 [101.6]	20.0 [508.0]	30.64 [778.3]
MC4500	1,000	200	250	1/2" VCR	6.0 [152.4]	27.64 [702.6]	38.3 [972.8]
MC9000	1,000	300	250	1/2" VCR	6.0 [152.4]	39.34 [999.7]	50.00 [1270.0]
MC14K	2,000	1,000	250	3/4" VCR	6.0 [152.4]	50.8 [1290]	67.1 [1705]
High Pressure Pu	rifiers						
HP190	50	5	1,000	1/4" VCR	2.0 [50.8]	8.2 [208.3]	13.80 [350.5]
HP400	60	9	1,000	1/4" VCR	3.0 [76.2]	8.2 [208.3]	13.80 [350.5]
HP700	120	25	1,000	1/4" VCR	3.0 [50.8]	10.0 [254.0]	15.6 [396.2]
HP3000	500	80	1,000	1/2" VCR	3.9[100.1]	20.0 [508.0]	28.9 [756]
SP70	40	1.5	3,000	1/4" VCR	2.0 [50.8]	5.00 [127.0]	10.60 [270.0]
SP300	200	10	3,000	1/4" VCR	2.0 [50.8]	15.00 [381.0]	20.60 [524.0]
SP600	400	15	3,000	1/4" VCR	2.0 [50.8]	25.00 [635.0]	30.60 [778.0]



LEADING EDGE MATERIALS FOR LEADING EDGE APPLICATIONS



Purification Media

Name	Common Gases	Media	All Gases Purified	Impurities Removed	Regenerable
H₂ 904 H₂, D₂, H₂/Inert Mixtures Organics, Acids, Refractory Compounds to <1 ppt; Bases < 5 ppt, Yes Metals < 1 ppb/ V Yes Metals < 1 ppb/ N Q₂, CDA (Clasan Dry Air or Compressed Dry Air) 203 N₂, Ar, He, Kr, Ne, Xe, H₂, D₂, CDA, O₂, N₂O Organics, Acids, Refractory compounds to <1 ppt; Bases < 5 ppt, Metals < 1 ppb/ Netals < 1 ppb	N ₂ Ar, He, Kr, Ne, Xe	902		Organics, Acids, Refractory Compounds to < 1 ppt; Bases < 5 ppt,	Yes
O _C , CDA (Clean Dry Air or Compressed Dry Air) 203 N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , D ₂ , CDA, O ₂ , N ₂ O Organics, Acids, Refractory Compounds to < 1 ppt, Bases < 5 ppt, Yes NH ₃ 702 NH ₂ , C ₂ H ₃ N ₁ , C ₂ H ₄ , C ₂ H ₄ , C ₃ H ₄ , CH ₄ , C	H_2	904	H ₂ , D ₂ , H ₂ /Inert Mixtures	Organics, Acids, Refractory Compounds to < 1 ppt; Bases < 5 ppt,	Yes
NH, NH, Process Process CDA, O _x , N _x O H _x O, CO, CO _x , NMHC to <1 ppb, Metals <1 ppbV Yes NH, Process NH _y C,H,N, C,H,N, C,H _x , C,H _x , C,H _x , C,H _x , GeH _x . Histures H _y O, O _x , CO _x , NMHCs, Metals to <1 ppb	(Clean Dry Air or	203	N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , D ₂ , CDA, O ₂ , N ₂ O	Organics, Acids, Refractory Compounds to < 1 ppt; Bases < 5 ppt,	Yes
Regentral AMC Removal Only 202 N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , D ₂ , CDA, O ₂ , N ₂ O Organics, Acids, Refractory Compounds to <1 ppt; Bases <5 ppt, Yes Netals <1 ppt) Netals <1 ppt) Yes Netals <1 ppt) N	Compressed Dry Air)	906	CDA, O ₂ , N ₂ O	H ₂ O, CO, CO ₂ , NMHC to < 1 ppb, Metals < 1 ppbV	Yes
CO₂ Organics, Acids, Refractory Compounds to <1 ppt, Bases <5 ppt, Yes Yes B05 CO₂ Organics, Acids, Refractory Compounds to <1 ppt, Bases <5 ppt, Wes	NH_3	702	$\begin{array}{c} {\rm NH_3,\ C_2H_7N,\ C_2H_8N_2,\ C_2H_4,\ C_3H_6,\ CH_3SiH_3,\ GeH_4,} \\ {\rm SF_6,\ H_2/SiH_4\ mixtures} \end{array}$	H ₂ O, O ₂ , CO ₂ , NMHCs, Metals to < 1 ppb	Yes
Removal Only 403 N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , D ₂ , CDA, O ₂ , N ₂ O Organics, Acids, Refractory Compounds to <1 ppt; Bases <5 ppt, Metals N ₂ Ar, He, Kr, Ne, Xe, H ₂ , D ₂ , CDA, O ₂ , N ₂ O Organics, Acids, Refractory Compounds to <1 ppt; Bases <5 ppt, Yes	60	804	CO ₂	Organics, Acids, Refractory Compounds to < 1 ppt; Bases < 5 ppt,	Yes
O2 N2, Ar, He, Kr, Ne, Xe, H2, D2, CDA, O2, N2O Organics, Acids, Refractory Compounds to <1 ppt; Bases <5 ppt, Metals <1 ppb Yes Application Specific Media Media All Gases Purified Impurities Removed Regeneral Dryer Only 202 N2, Ar, He, Kr, Ne, Xe, H2, D2, CDA, O2, CO2, N2O H2,O to <1 ppb	CO ₂ -	805	CO ₂	Organics, Acids, Refractory Compounds to < 1 ppt; Bases < 5 ppt,	Yes
Application Specific Media All Gases Purified Impurities Removed Regeneral Media Dryer Only 202 N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , D ₂ , CDA, O ₂ , CO ₂ , N ₂ O H ₂ O to <1 ppb Yes Dryer and AMC Removal Only 403 N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂ Organics, Acids, Refractory Compounds to <1 ppt, Bases <5 ppt, Metals <1 ppb Organic Removal Only 404 N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂ Organics, Acids, Refractory Compounds to <1 ppt, Bases <5 ppt, Metals <1 ppb Organic Removal Only 404 N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂ Organics, Acids, Refractory Compounds to <1 ppt, Bases <5 ppt, No Metals <1 ppb Organic Removal Only 404 N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂ Organics, Acids, Refractory Compounds to <1 ppt, Bases <5 ppt, No Organic Removal Only 404 N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂ C ₂ H ₂ , C ₂ H ₃ , C ₃ H ₆ , C ₄ H ₄ , NH ₃ Organic Removal Only 405 N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂ , C ₂ H ₂ , C ₂ H ₂ , C ₃ H ₆ , C ₄ H ₄ , NH ₃ Organic Removal Only 406 N ₂ , H ₃ S, H ₃ S, H ₃ S, H ₃ S, C ₄ H ₄ , NH ₃ Organic Removal Only 407 N ₂ NO, SiCl ₄ , SiH ₂ Cl ₂ , S	Ο,	203	N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , D ₂ , CDA, O ₂ , N ₂ O	Organics, Acids, Refractory Compounds to < 1 ppt; Bases < 5 ppt,	Yes
Media Media All Gases Purified Impurities Removed Regeleration Dryer Only 202 N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , D ₂ , CDA, O ₂ , CO ₂ , N ₂ O H ₂ O to <10 ppt	-	906	CDA, O ₂ , N ₂ O	H ₂ O, CO, CO ₂ , NMHC to < 1 ppb, Metals < 1 ppbV	Yes
Dryer and AMC Removal 203 N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , D ₂ , CDA, O ₂ , N ₂ O Organics, Acids, Refractory Compounds to <1 ppt; Bases < 5 ppt, Metals <1 ppb Yes AMC Removal Only 403 N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂ Organics, Acids, Refractory Compounds to <1 ppt; Bases < 5 ppt, Metals <1 ppb		Media	All Gases Purified	Impurities Removed	Regenerable
Privar and AMC Removal 203 N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , D ₂ , CDA, O ₂ , N ₂ O Organics, Acids, Refractory Compounds to <1 ppt; Bases <5 ppt, Metals <1 ppb AMC Removal Only 403 N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂ Organics, Acids, Refractory Compounds to <1 ppt; Bases <5 ppt, Metals <1 ppb No Organic Removal Only 404 N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂ C ₃ H ₆ , C ₂ H ₄ , NH ₃ Corrosive Gases 302 HC, Cl ₂ , B ₂ H ₆ , BCl ₃ , CClH ₃ , CO ₂ , GeCl ₄ , GeH ₄ , HCl, Cl ₂ , B ₂ H ₆ , BCl ₃ , CClH ₃ , CO ₂ , GeCl ₄ , SiH ₂ Cl ₂ , SiHCl ₃ , SO ₂ , CHClF ₂ , BF ₃ , NO, NF ₃ , NO, SiCl ₄ , SiF ₄ , SiH ₂ Cl ₂ , SiHCl ₃ , SO ₂ Arsine and Phosphine 502 AsH ₃ , PH ₃ Drygen Conversion (De-Oxo) 503 H ₂ , Ar, He, N ₂ , CO ₂ with 1% O ₂ CO H ₂ O, O ₂ , CO ₂ , Acids, Bases, Organics, Refractories, Metals <1 ppbV No Carbon Monoxide (CO) 602 CO H ₂ O, O ₂ , CO ₂ , Acids, Bases, Organics, Refractories, Metals <1 ppbV No	Dryer Only	202	N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , D ₂ , CDA, O ₂ , CO ₂ , N ₂ O	H ₂ O to < 1 ppb	Yes
AMC Removal Only 403 N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂ Metals < 1 ppb No Organic Removal Only 404 N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂ , C ₂ H ₂ , C ₃ H ₆ , C ₂ H ₄ , NH ₃ P(Corrosive Gases) Arsine and Phosphine 502 AsH ₃ , PH ₃ AsH ₃ , PH ₃ H ₂ O, O ₂ to < 1 ppb, Metals < 1 ppb No Oxygen Conversion (De-Oxo) 503 H ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂ Ar, NH ₂ , CD ₃ NH ₂ O, O ₂ to < 1 ppb, Metals < 1 ppb No No No Oxygen Conversion (De-Oxo) 602 CO H ₂ O, O ₂ , CO ₂ , Acids, Bases, Organics, Refractories, Metals < 1 ppbV No				H ₂ O, CO ₂ to < 100 ppt;	
Corrosive Gases 302 HCI, Cl ₂ , B ₂ H ₆ , BCI ₃ , CCIH ₃ , CO ₂ , GeCl ₄ , GeH ₄ , H ₂ S, H ₂ Se, HBr, N ₂ O, NF ₃ , NO, SiCl ₄ , SiH ₂ Cl ₂ , SiHCl ₃ , SO ₂ , CHCIF ₂ , BF ₃ , N ₂ O, NF ₃ , NO, SiCl ₄ , SiH ₂ Cl ₂ , SiHCl ₃ , SO ₂ H ₂ O, Metals to < 1 ppb No Arsine and Phosphine 502 AsH ₃ , PH ₃ H ₂ O, O ₂ to < 1 ppb, Metals < 1 ppbV	Removal	203	$\mathrm{N_2},\mathrm{Ar},\mathrm{He},\mathrm{Kr},\mathrm{Ne},\mathrm{Xe},\mathrm{H_2},\mathrm{D_2},\mathrm{CDA},\mathrm{O_2},\mathrm{N_2O}$		Yes
Corrosive Gases 302 HCI, CI ₂ , B ₂ H ₈ , BCI ₃ , CCIH ₃ , CO ₂ , GeCI ₄ , GeH ₄ , H ₂ S, H ₂ Se, HBr, N ₂ O, NF ₃ , NO, SiCI ₄ , SiH ₂ CI ₂ , SiHCI ₃ , SO ₂ , CHCIF ₂ , BF ₃ , N ₂ O, NF ₃ , NO, SiCI ₄ , SiH ₂ CI ₂ , SiHCI ₃ , SO ₂ H ₂ O, Metals to < 1 ppb No Arsine and Phosphine 502 AsH ₃ , PH ₃ H ₂ O, O ₂ to < 1 ppb, Metals < 1 ppbV				Metals < 1 ppb Organics, Acids, Refractory Compounds to < 1 ppt; Bases < 5 ppt,	
Oxygen Conversion (De-Oxo) 503 H ₂ , Ar, He, N ₂ , CO ₂ with 1% O ₂ O ₂ to < 1 ppm N/A Carbon Monoxide (CO) 602 CO H ₂ O, O ₂ , CO ₂ , Acids, Bases, Organics, Refractories, Metals < 1 ppbV No	AMC Removal Only	403	N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂	Metals < 1 ppb Organics, Acids, Refractory Compounds to < 1 ppt; Bases < 5 ppt, Metals < 1 ppb	No
Carbon Monoxide (CO) 602 CO H ₂ O, O ₂ , CO ₂ , Acids, Bases, Organics, Refractories, Metals < 1 ppbV No	AMC Removal Only Organic Removal Only	403	N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂ N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂ , C ₂ H ₂ , C ₃ H ₆ , C ₂ H ₄ , NH ₃ HCl, Cl ₂ , B ₂ H ₆ , BCl ₃ , CClH ₃ , CO ₂ , GeCl ₄ , GeH ₄ , H ₂ S, H ₂ Se, HBr, N ₂ O, NF ₃ , NO, SiCl ₄ , SiF ₄ , SiH ₂ Cl ₂ , SiHCl ₃ , SO ₂ , CHClF ₄ , BF ₄ , NO, NF ₄ , NO, SiCl ₄ .	Metals < 1 ppb Organics, Acids, Refractory Compounds to < 1 ppt; Bases < 5 ppt, Metals < 1 ppb Organics < 1 pptV	No Yes
	AMC Removal Only Organic Removal Only Corrosive Gases	403 404 302	N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂ N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂ , C ₂ H ₂ , C ₃ H ₆ , C ₂ H ₄ , NH ₃ HCl, Cl ₂ , B ₂ H ₆ , BCl ₃ , CClH ₃ , CO ₂ , GeCl ₄ , GeH ₄ , H ₂ S, H ₂ Se, HBr, N ₂ O, NF ₃ , NO, SiCl ₄ , SiF ₄ , SiH ₂ Cl ₂ , SiHCl ₃ , SO ₂ , CHClF ₂ , BF ₃ , N ₂ O, NF ₃ , NO, SiCl ₄ , SiF ₄ , SiH ₂ Cl ₂ , SiHCl ₃ , SO ₂	Metals < 1 ppb Organics, Acids, Refractory Compounds to < 1 ppt; Bases < 5 ppt, Metals < 1 ppb Organics < 1 pptV H ₂ O, Metals to < 1 ppb	No Yes No
Silane (SiH ₄) 802 SiH ₄ H ₂ O, O ₂ , CO, CO ₂ , Sulphur compounds, Metals removal < 1 ppb No	AMC Removal Only Organic Removal Only Corrosive Gases Arsine and Phosphine Oxygen Conversion	403 404 302 502	N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂ N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂ , C ₂ H ₂ , C ₃ H ₆ , C ₂ H ₄ , NH ₃ HCl, Cl ₂ , B ₂ H ₆ , BCl ₃ , CClH ₃ , CO ₂ , GeCl ₄ , GeH ₄ , H ₂ S, H ₂ Se, HBr, N ₂ O, NF ₃ , NO, SiCl ₄ , SiF ₄ , SiH ₂ Cl ₂ , SiHCl ₃ , SO ₂ , CHClF ₂ , BF ₃ , N ₂ O, NF ₃ , NO, SiCl ₄ , SiF ₄ , SiH ₂ Cl ₂ , SiHCl ₃ , SO ₂ ASH ₃ , PH ₃	$\label{eq:metals} Metals < 1 \ ppb$ $\label{eq:metals} Organics, Acids, \ Refractory Compounds to < 1 \ ppt; \ Bases < 5 \ ppt, \\ Metals < 1 \ ppb$ $\label{eq:metals} Organics < 1 \ pptV$ $\label{eq:metals} H_2O, \ Metals \ to < 1 \ ppb$ $\label{eq:metals} H_2O, \ O_2 \ to < 1 \ ppb, \ Metals < 1 \ ppbV$	No Yes No
	AMC Removal Only Organic Removal Only Corrosive Gases Arsine and Phosphine Oxygen Conversion (De-Oxo)	403 404 302 502 503	N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂ N ₂ , Ar, He, Kr, Ne, Xe, H ₂ , CDA, O ₂ , CO ₂ , C ₂ H ₂ , C ₃ H ₆ , C ₂ H ₄ , NH ₃ HCl, Cl ₂ , B ₂ H ₆ , BCl ₃ , CClH ₃ , CO ₂ , GeCl ₄ , GeH ₄ , H ₂ S, H ₂ Se, HBr, N ₂ O, NF ₃ , NO, SiCl ₄ , SiF ₄ , SiH ₂ Cl ₂ , SiHCl ₃ , SO ₂ , CHClF ₂ , BF ₃ , N ₂ O, NF ₃ , NO, SiCl ₄ , SiF ₄ , SiH ₂ Cl ₂ , SiHCl ₃ , SO ₂ ASH ₃ , PH ₃ H ₂ , Ar, He, N ₂ , CO ₂ with 1% O ₂	Metals < 1 ppb Organics, Acids, Refractory Compounds to < 1 ppt; Bases < 5 ppt, Metals < 1 ppb Organics < 1 pptV H_2O , Metals to < 1 ppb H_2O , O_2 to < 1 ppb, Metals < 1 ppbV O_2 to < 1 ppm	No Yes No No





ENVIRONMENTALLY FRIENDLY SOLUTIONS

MicroTorr Options

Regeneration

Many MicroTorr purifiers can be sent back to the SAES Pure Gas factory for regeneration. Regeneration minimizes hazardous waste and is an environmentally friendly solution. All specified impurities are removed during the regeneration process. After regeneration the purifier will have the same lifetime as a new purifier.

How long is the lifetime?

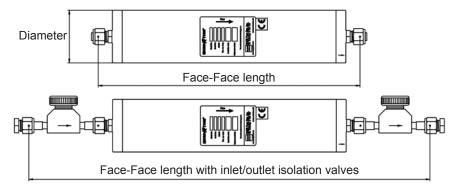
MicroTorr Purifiers are designed for the maximum lifetime to reduce the frequency of purifier change-out and provide customers with the highest cost of ownership possible. In general the lifetime is 1 year with standard 5N (99.999%) quality gas, at the average flow rating of the purifier. To attain an application specific lifetime calculation please consult SAES Pure Gas, with your flow rate and inlet impurity information.

0.003µm Particle Filter (F)

This sintered metal particle filter is located inside the purifier at the outlet. The particle filter is optimized for a low pressure drop.

■ Inlet and Outlet Isolation Valves (V)

The isolation valves provides for a simple installation and minimizes the risk of exposing the purifier to atmosphere during installation. See the 'Purifier Sizes' table for the length of each model with or without the isolation valves.



Dual Purifier Manifold

The purifiers can flow individually or in parallel. Each purifier can be isolated so it can be replaced or sent to the SAES Pure Gas factory for regeneration. The Manifold includes a backing plate to easily mount the assembly. Inlet and outlet connections are both on top for a simple installation.

3 Valve Bypass Piping

Allows the user to bypass and isolate the purifier for replacement or regeneration. Purifier is removed without any valves attached.

■ 5 Valve Bypass Piping

Allows the user to bypass and isolate the purifier for replacement or regeneration. Purifier is removed with inlet and outlet valves attached.



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